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PATENT ABSTRACTS OF JAPAN

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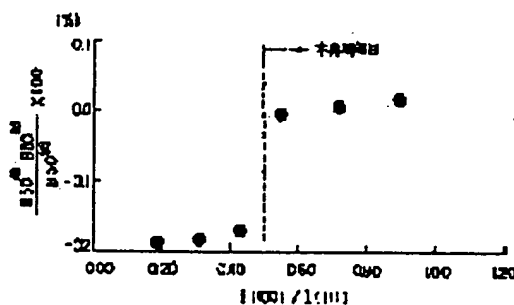
(71)Applicant : NIPPON STEEL CORP

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YAMADA KENJI**(54) NONORIENTED SILICON STEEL SHEET HAVING HIGH MAGNETIC FLUX DENSITY AFTER STRESS RELIEF ANNEALING****(57)Abstract:**

PURPOSE: To produce a nonoriented silicon steel sheet having high magnetic flux density after stress relief annealing by forming a texture, satisfying the prescribed conditions, in a steel sheet before stress relief annealing, in a nonoriented silicon steel sheet containing specific amounts of Si and C.

CONSTITUTION: A nonoriented silicon steel sheet, containing, by weight, $\leq 7.00\%$ Si and $\leq 0.010\%$ C in steel and used for iron core for use in electrical equipment, such as rotary machine iron core and transformer iron core, is provided, before stress relief annealing, with a texture in which $I(100)$ and $I(111)$ as the values of the ratios of the X-ray reflected surface intensities of (100) and (111) orientations in the pseudoplane parallel to a sheet surface in the part between the surface layer and a position at a depth one-fifth the sheet thickness from the surface layer to a random texture, satisfy relational inequality $0.50 \leq I(100)/I(111)$. By this method, the nonoriented silicon steel sheet having high magnetic flux density after stress relief annealing can be obtained.

**LEGAL STATUS**

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